

Notice of References Cited	Application/Control No. 10/624,384	Applicant(s)/Patent Under Reexamination LEYBOVICH, ALEXANDER	
	Examiner Rodney G. McDonald	Art Unit 1753	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,734,340	03-1988	Saito et al.	428/701
	B	US-			
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	D	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Albertinetti et al. "Granularity in ion-beam-sputtered TiO ₂ films", Applied Optics, Vol. 35, No. 28, 1 October 1996, pp. 5620-5625.
	V	Harper et al. "Technology and applications of broad-beam ion sources used in sputtering. Part II. Applications", J. Vac. Sci. Technol., 21(3), sept/Oct 1982 pp. 737-756.
	W	Mattox "Handbook of Physical Vapor Deposition (PVD) Processing- Film Formation, Adhesion, Surface Preparation and Contamination Control", 1998 pp. 344, 385.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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